	L #	Hits	Search Text
1	L1	117114	(mask or reticle or (optical adj tool)) and (substrate or wafer)
2	L2	24016	focus\$3 and 1
3	L3	1162	(mask or reticle or (optical adj tool)) same (opaque and transparent and phase)
4	L4	1162	(mask or reticle or (optical adj tool)) same (opaque and transparent and phase)
5	L5	660	2 and 4
6	L6	525	5 and (355/\$.ccls. or 430/\$.ccls. or 250/\$.ccls. or 356/\$.ccls. or 396/\$.ccls.)
7	L7	469	@ad<=20010831 and 6
8	L8	512183	lens or projection
9	L9	380	7 and 8
10	L10	380	9 and focus\$3
11	L11	1251	(mask or reticle or (optical adj tool)) same ((opaque and transparent) near4 (portion or region or line or area))
12	L12	1272	(mask or reticle or (optical adj tool) or quartz) same ((opaque and transparent) near4 (portion or region or line or area))

	L #	Hits	Search Text
13	L13	4384	(mask or reticle or (optical adj tool) or quartz) same (phase near5 (chang\$3 or shift\$3))
14	L14	299	12 and 13
15	L15	29526	(lens or projection) same focus\$3 same (wafer or substrate or object)
16	L16	22767	image same (position\$3 or move or moving or moved or movement or locat\$4) same (wafer or substrate or object) same (lens or projection)
17	L17	33	15 and 16 and 14
18	L18	2	944795.ap.

Akr 6/3/23